



2020년 2월 14일(금), 10:45~12:30

Room K (다이아몬드 I, 6층)

D. Thin Film Process Technology 분과

[FK2-D] Thin Film Process III

FK2-D-1 10:45~11:15	<p>[초청]</p> <p>Atomic Layer Deposition Assisted Double Patterning Lithography Se-Hun Kwon <i>School of Materials Science and Engineering, Pusan National University</i></p>
FK2-D-2 11:15~11:30	<p>Chemical and Electrical Properties of Atomic Layer Deposited HfO₂ Using Hf(N(CH₃)₂)₄ and CpHf(N(CH₃)₂)₃ Precursors Sungmin Park¹, Bo-Eun Park¹, Hwi Yoon¹, Sanghun Lee¹, Taewook Nam¹, Taehoon Cheon², Soo-Hyun Kim², and Hyungjun Kim¹ ¹<i>School of Electrical and Electronics Engineering, Yonsei University, </i>²<i>School of Materials Science and Engineering, Yeungnam University</i></p>
FK2-D-3 11:30~11:45	<p>Carbon Nanotube Network Transistors Constructed from the Reuse of Semiconducting Carbon Nanotube Solution Ju Won Jeon¹, Yongwoo Lee¹, Jinsu Yoon¹, Hyo-Jin Kim¹, Geon-Hwi Park¹, Dong Myong Kim¹, Dae Hwan Kim¹, Min-Ho Kang², and Sung-Jin Choi¹ ¹<i>School of Electrical Engineering, Kookmin University, </i>²<i>Department of Nano-process, National Nanofab Center(NNFC)</i></p>
FK2-D-4 11:45~12:00	<p>Diffusion of Vanadium and Yttrium is Responsible for the Degradation of Vanadium Oxide Films Deposited on Y-stabilized ZrO₂ Above 500°C Songhee Choi¹, J. Oh², J.-H. Lee², J. H. Jang², and Shinbuhm Lee¹ ¹<i>DGIST, </i>²<i>KBSI</i></p>
FK2-D-5 12:00~12:15	<p>Atomic Layer Deposition of GeTe/Sb₂Te₃ Superlattice for Phase Change Memory Chanyoung Yoo, Woohyun Kim, Eui-sang Park, Manick Ha, Jeong Woo Jeon, Yoon Kyeong Lee, and Cheol Seong Hwang <i>Department of Materials Science and Engineering and Inter-University Semiconductor Research Center, Seoul National University</i></p>
FK2-D-6 12:15~12:30	<p>Tunable Diode Characteristics of Graphene via DUV Irradiations Asif Ali, Muhammad Hussain, Syed Hassan Abbas Jaffery, and Jung Jongwan <i>Department of Nanotechnology & Advanced Materials Engineering and Graphene Research Institute, Sejong University</i></p>